



Docket No.: 0941-0872P  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re Patent Application of:  
Chi-Wen LIU et al.

Application No.: 10/724,201

Confirmation No.: 8748

Filed: December 1, 2003

Art Unit: 2813

For: METHOD OF REDUCING THE PATTERN  
EFFECT IN THE CMP PROCESS

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Examiner: T. S. Pham

**FIRST PRELIMINARY AMENDMENT**

MS RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In reply to the Final Office Action dated March 7, 2006, and in view of the Request for Continued Examination being filed concurrently herewith, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This reply includes:

Amendments to the Claims; and

Remarks.